Fourth Semester M. Tech. Degree Examination, Dec. 2017/Jan. 2018 **Advances in VLSI Design**

Time: 3 hrs.

Max. Marks:100

Note: Answer any FIVE full questions.

- Describe with suitable mathematical analysis, the transfer plot of CMOS inverter and also explain the role of aspect ratios of n-channel and p-channel MOSFET's in CMOS device.
 - With the help of energy band diagrams, explain the working of MESFET under (i) Thermal equilibrium (ii) Forward bias (iii) Reverse bias.
- Explain the basic principles of modulation doping with the help of energy band diagrams and hence explain the operations of HEMT device structure formed using GaAs and (08 Marks) AlGaAs.
 - b. List the ideal properties of MIS systems.

(04 Marks)

- c. A JFET has $N_a=10^{19}\,\text{cm}^{-3}$, $N_a=10^{16}\,\text{cm}^{-3}$, $a=0.1\,\mu\text{m}$, $L=10\,\mu\text{m}$ and $Z=1\,\text{mm}$. Assume that the device is S_i with an intrinsic concentration of 10¹⁰ cm⁻³ and a relative dielectric constant of 11.8. Assume also that in saturation the square law can be used and that the value of I_{D_0} is 5 μ A. Calculate $\mathcal{O}(i)$ Built-in voltage (ii) Pinch off voltage (iii) V_{D_gSat} if $V_G = -2V$ (iv) Drain current if $V_D = 1V$ and $V_G = -2V$. $\frac{KT}{q} = 0.0259, n_i = 10^{10} \text{ cm}^{-3}, q = 1.6 \times 10^{-19}, c_0 = 8.85 \times 10^{-14} \text{ F/cm}.$ (08)
- Derive an expression for the threshold voltage of an MIS device and hence explain 3 (08 Marks) enhancement and depletion modes of operation.
 - Briefly discuss the sources of oxide charges and hence define flat band voltage.

(06 Marks)

Calculate the minimum capacitance for an n-channel (p-type) MIS capacitor. Assume that the capacitor is made from the Si-SiO-Al materials system. The p-type doping concentration within the semiconductor N_a is 5×10^{16} cm⁻³, the oxide thickness d is 12 nm, the insulator relative dielectric constant is 3.9, intrinsic concentration is 1010 cm 3, semiconductor relative dielectric constant is 11.8, $\frac{KT}{q} = 0.0259 \text{ V}$ and $\epsilon_0 = 8.85 \times 10^{-14} \text{ F/cm}$, $n_1 = 10^{10} \text{ cm}^{-3}$.

Show that in a short channel FET, the drain current is less than that in a long channel FET due to high electric field.

Briefly explain the processing challenges to further CMOS miniaturization. b.

- Show that the threshold voltage and drain current scale linearly with dimensions and voltage (06 Marks) in constant electric field scaling method.
- a. Describe the construction and working of SOI MOSFET. Also discuss its advantages over 5 (08 Marks) conventional MOSFET.
 - What is tactile computing? With examples, compare tactile computing with conventional (04 Marks)
 - Sketch the molecular diode energy levels under equilibrium, forward bias and reverse bias. (08 Marks) Explain each in brief.

Explain the working of nMOS inverting super buffer with the help of a neat circuit diagram and stick diagram. (04 Marks) Realize 2-input NAND gate using BiCMOS gates. b. With the help of truth table, K-map and nMOS realization, design pass transistor logic for, (ii) 2-input EXOR gate. (i) 2-input NOR gate Derive an expression for propagation delay in terms of capacitive load (CL), gate capacitance (Cg) for a 2-input NOR gate driving a super buffers for different fanout values. (06 Marks) Explain the conceptual layout of 3-input tally circuits. Draw the stick diagram for pass (08 Marks) transistor based 3-input tally circuit. With a neat diagram, explain the CMOS implementation of 4 multiplexer. (06 Marks) b. (06 Marks) Explain with an example, line search algorithm. Explain the following terms with an example each: 8 (iii) Modularity (10 Marks) (iv) Locality. (ii) Regularity (i) Hierarchy What is programmable logic? Explain programmable logic structures with diagrams. b. (10 Marks)